

Title (en)

ACTIVE-LIGHT-SENSITIVE OR RADIATION-SENSITIVE RESIN COMPOSITION, ACTIVE-LIGHT-SENSITIVE OR RADIATION-SENSITIVE FILM, PATTERN FORMATION METHOD, METHOD FOR MANUFACTURING ELECTRONIC DEVICE, ACTIVE-LIGHT-SENSITIVE OR RADIATION-SENSITIVE RESIN COMPOSITION FOR MANUFACTURING PHOTOMASK, AND METHOD FOR MANUFACTURING PHOTOMASK

Title (de)

AKTIV-LICHTEMPFFINDLICHE ODER STRAHLUNGSEMPFFINDLICHE HARZZUSAMMENSETZUNG, AKTIV-LICHTEMPFFINDLICHER ODER STRAHLUNGSEMPFFINDLICHER FILM, MUSTERBILDUNGSVERFAHREN, VERFAHREN ZUM HERSTELLEN EINER ELEKTRONISCHEN VORRICHTUNG, AKTIV-LICHTEMPFFINDLICHE ODER STRAHLUNGSEMPFFINDLICHE HARZZUSAMMENSETZUNG ZUM HERSTELLEN EINER FOTOMASKE, UND VERFAHREN ZUM HERSTELLEN EINER FOTOMASKE

Title (fr)

COMPOSITION DE RÉSINE SENSIBLE À LA LUMIÈRE ACTIVE OU SENSIBLE AU RAYONNEMENT, FILM SENSIBLE À LA LUMIÈRE ACTIVE OU SENSIBLE AU RAYONNEMENT, PROCÉDÉ DE FORMATION DE MOTIF, PROCÉDÉ DE FABRICATION DE DISPOSITIF ÉLECTRONIQUE, COMPOSITION DE RÉSINE SENSIBLE À LA LUMIÈRE ACTIVE OU SENSIBLE AU RAYONNEMENT POUR FABRIQUER UN PHOTO-MASQUE, ET PROCÉDÉ DE FABRICATION DE PHOTO-MASQUE

Publication

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Application

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Priority

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Abstract (en)

[origin: EP4130878A1] According to the present invention, it is possible to provide an actinic ray-sensitive or radiation-sensitive resin composition containing a resin of which a solubility in a developer changes by the action of an acid, a photoacid generator (A) that has a group having a polarity which changes through decomposition by the action of an acid, a photoacid generator (B) that generates an acid having a higher pKa than an acid generated from the photoacid generator (A), and a basic compound; and an actinic ray-sensitive or radiation-sensitive film, a pattern forming method, a method for manufacturing an electronic device, an actinic ray-sensitive or radiation-sensitive resin composition for manufacturing a photomask, and a method for manufacturing a photomask, each of which uses the composition.

IPC 8 full level

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Citation (search report)

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- See references of WO 2021200056A1

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DOCDB simple family (application)

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